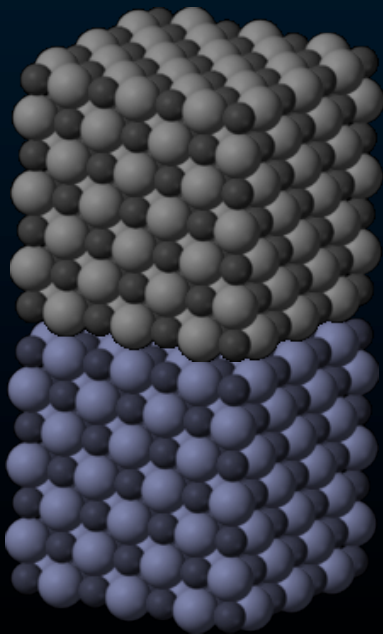


DOPED SEMICONDUCTORS AND CERAMIC MATERIALS: NEW PLATFORM FOR PLASMONICS



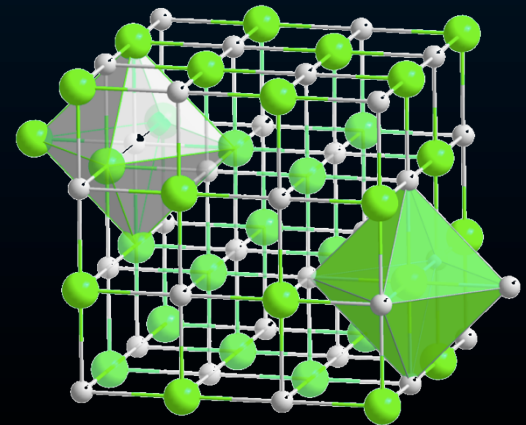
*BUILDING NANOSCALE PHOTONIC
TECHNOLOGIES OF THE FUTURE*

Alexandra Boltasseva

School of Electrical & Computer Engineering
Birck Nanotechnology Center
PURDUE UNIVERSITY

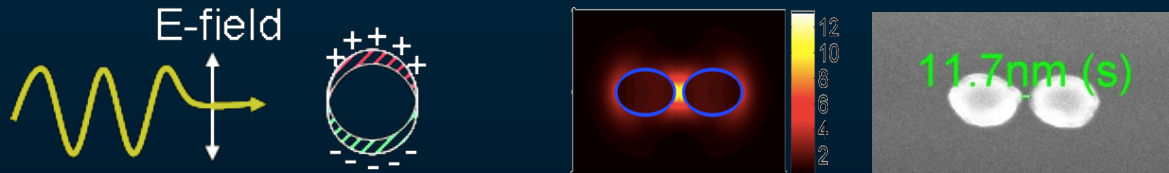
OUTLINE

- Introduction: Plasmonics & Metamaterials
- Material Requirements: Challenges with Gold and Silver
- Alternative Materials?
- Transparent Conducting Oxides
- Transition Metal Nitrides
- Figures of Merit and Applications
- CMOS- and Refractory Plasmonics
- Outlook

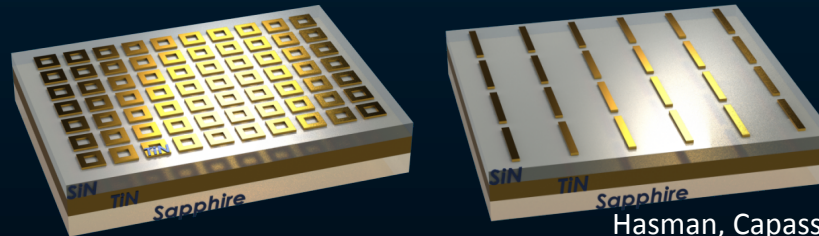


PLASMONICS

1 Localized SP = Optical Nano-Antenna (imaging, sensing, therapy, energy...)

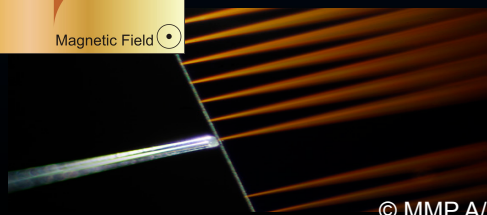
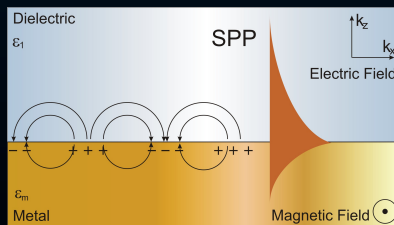


= **Optical Metasurfaces** (ultra-thin/flat optics, sensors...)

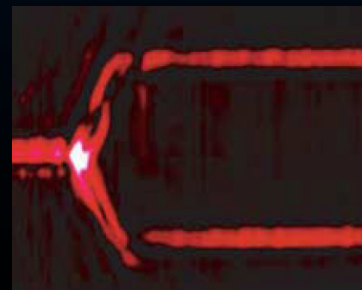


Hasman, Capasso, Zheludev, Alu and others

2 Propagating SP = Nano-Waveguide (integrated photonics, sensors...)

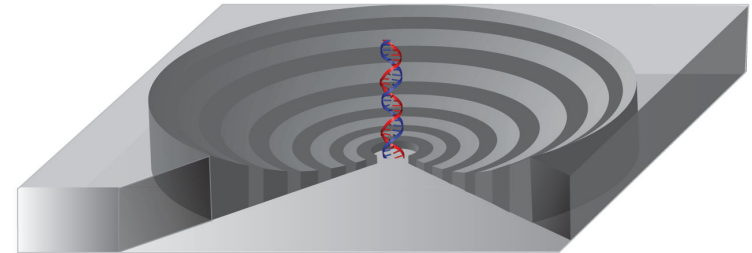
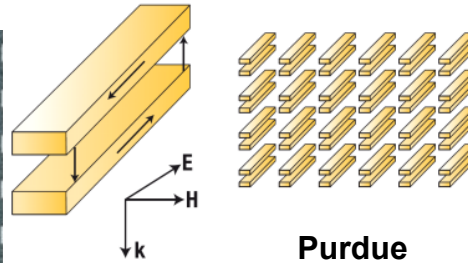
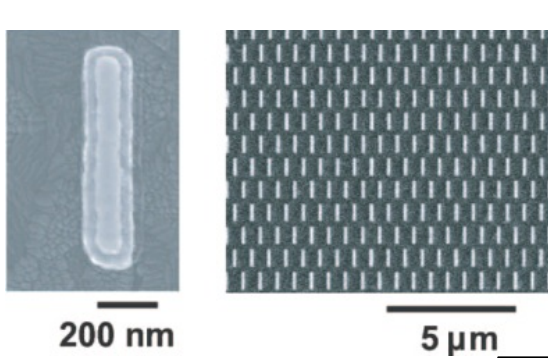


© MMP A/S

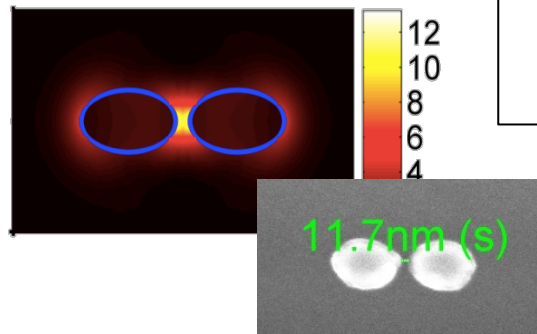


S. I. Bozhevolnyi, et al., Nature 404 (2006)

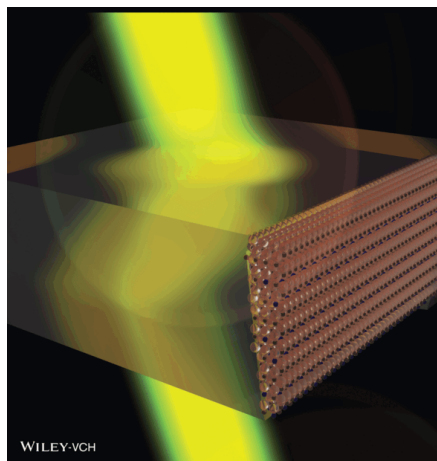
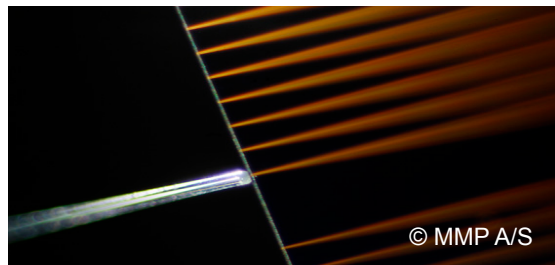
PLASMONICS/METAMATERIALS/TO



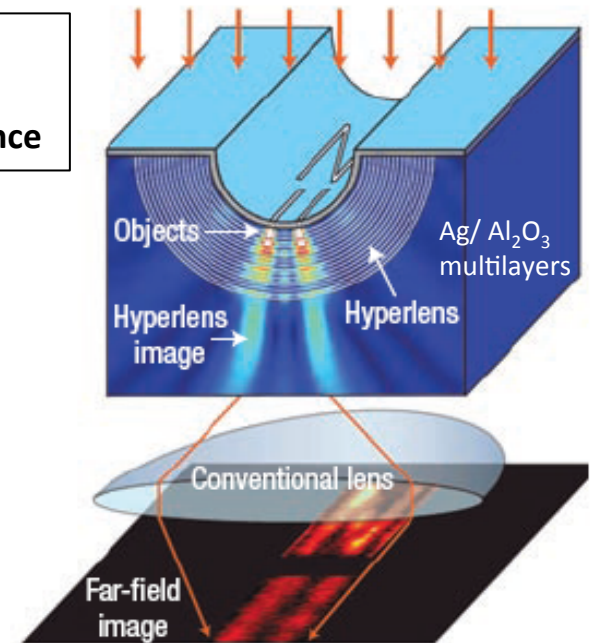
Narimanov, Engheta



Plasmonics and metamaterials offer an unprecedented ability to control light
Numerous examples of extraordinary science



Purdue



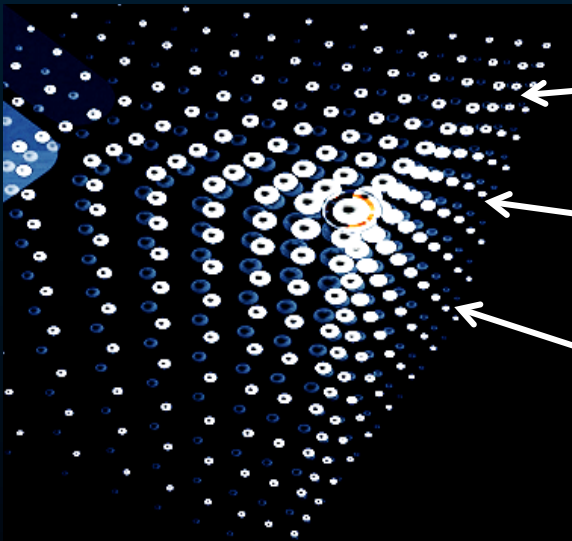
Z. Liu et. al, Science (2007)

METAMATERIALS

size $\ll \lambda$

METAMATERIALS

POSSIBILITIES are VAST!



PERIOD/ARRANGEMENT

GEOMETRY/UNIT CELL DESIGN

MATERIALS

Metamaterial is an arrangement of artificial structural elements, designed to achieve advantageous and/or unusual properties

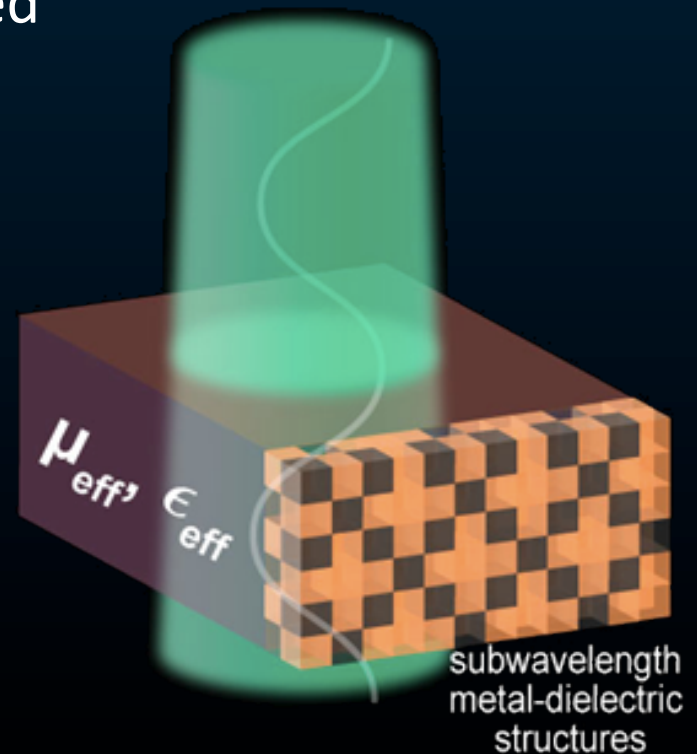
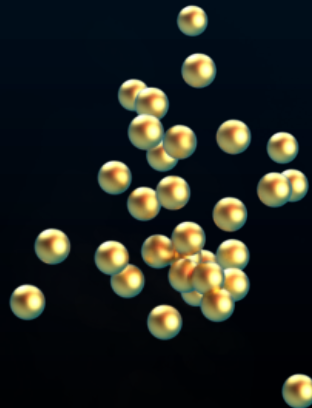
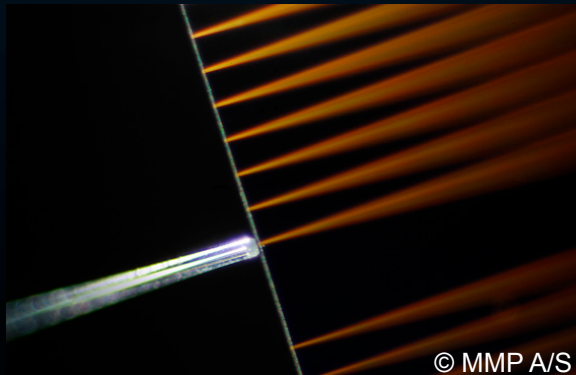
$\mu\epsilon\tau\alpha$ = meta = beyond (Greek)

MAKING REAL DEVICES

PLASMONICS AND METAMATERIALS:
PLENTY OF WONDERFUL DESIGNS AND IDEAS!

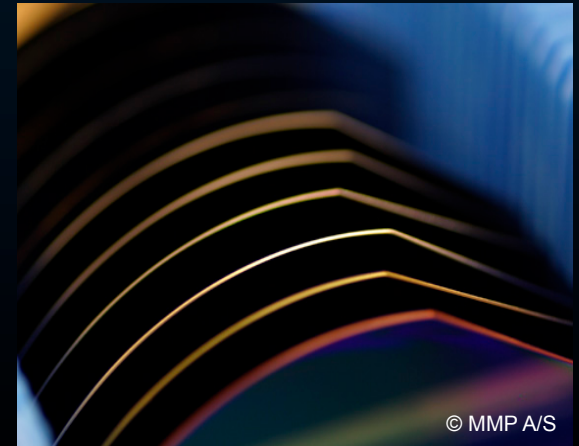
We would normally mix **metals** and **dielectrics** and arrange in a predesigned fashion

What about constituent materials?



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MATERIALS

We want:

- Low loss devices
- Switchable / Tunable devices
- SC-compatible components
- Low cost, robust, stable

- GOLD and SILVER used so far...
 - Large losses in the VIS/NIR
 - Fabrication challenges (continuous thin films)
 - Nanopatterning increases losses
 - Not tunable/adjustable optical properties
 - Not CMOS-compatible
 - High cost
 - Soft, low melting point

CHALLENGES

Conventional materials: Gold and Silver

- Large losses in near-IR and visible ranges

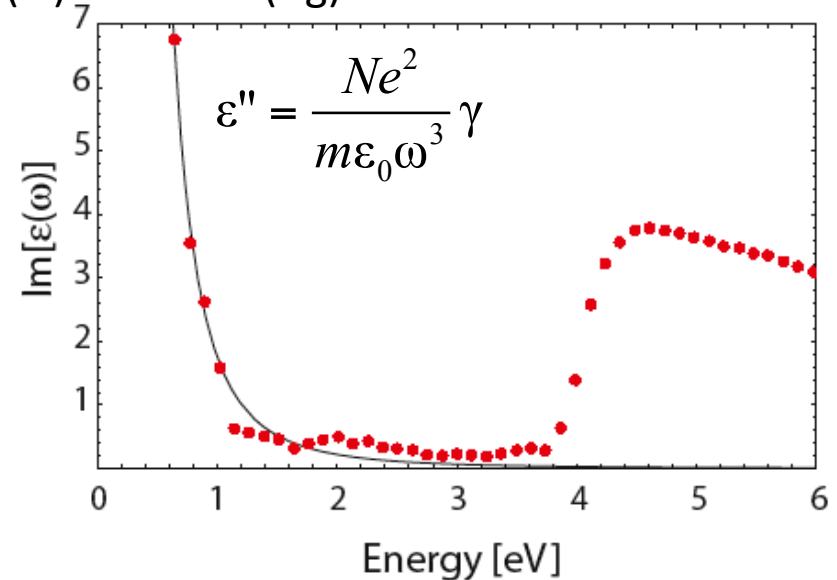
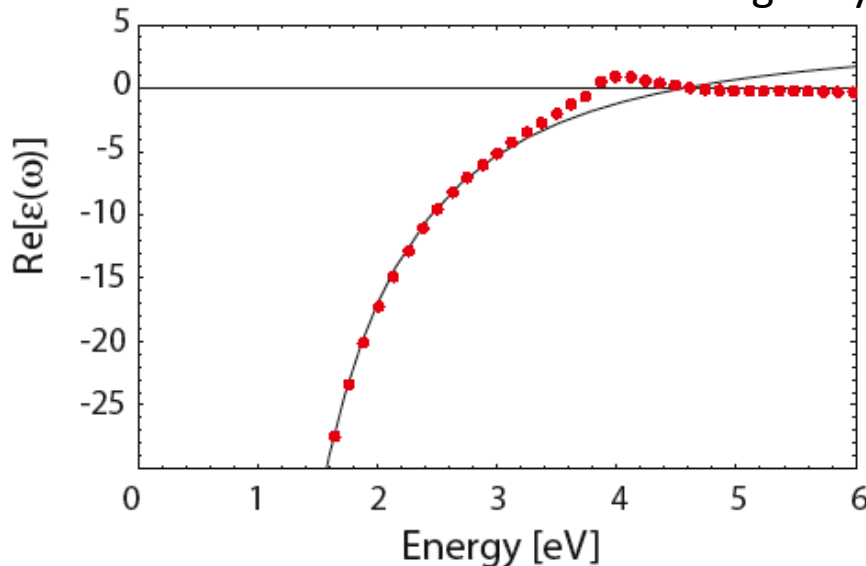
Interband transitions

Surface roughness, grain boundaries, etc...

$$\epsilon(\omega) = \epsilon_{ib} - \frac{Ne^2 / m\epsilon_0}{\omega^2 + i\omega\gamma_m(\omega)}$$

$$\epsilon(\omega) = \epsilon' + i\epsilon'' = \epsilon_b - \frac{\omega_p^2}{(\omega^2 + \gamma^2)} + i \frac{\omega_p^2 \gamma}{(\omega^2 + \gamma^2)\omega}$$

Real and Imaginary $\epsilon(\omega)$ for Silver (Ag)

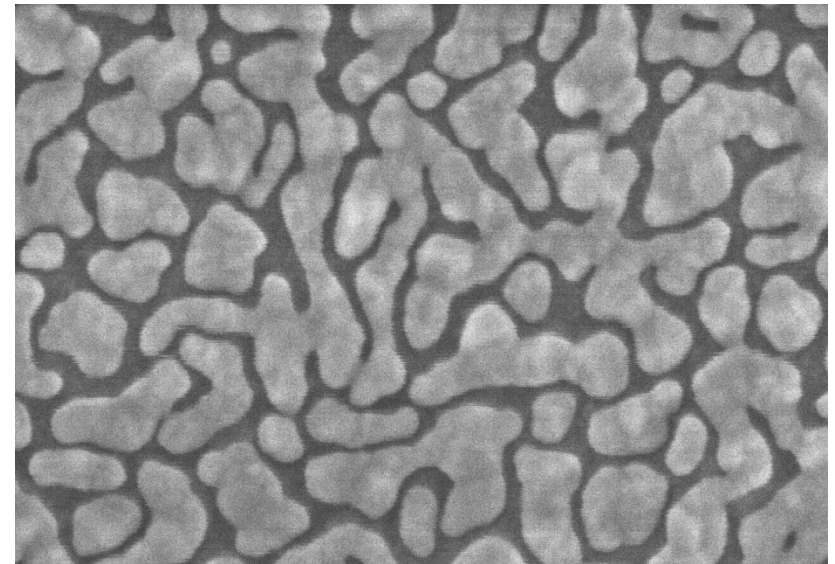
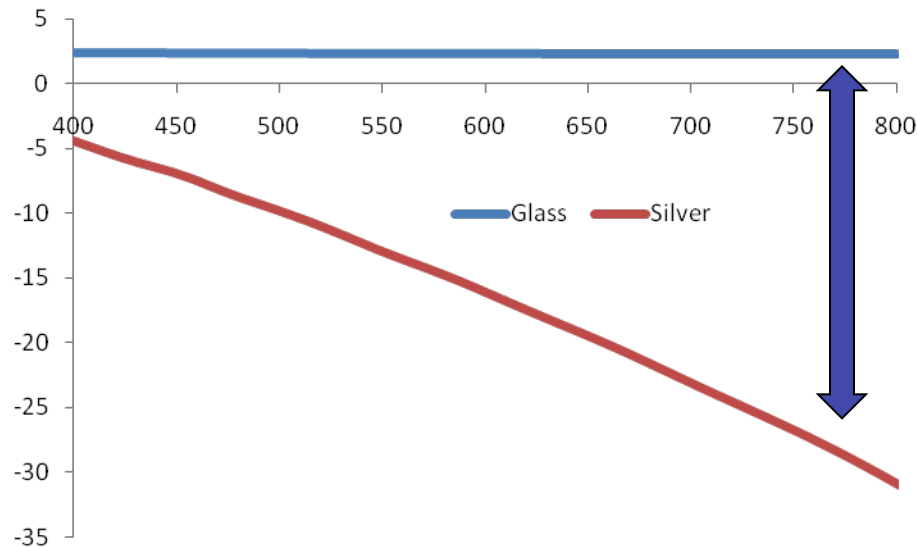


Johnson and Christy (dots) (1972)

Stefan Maier, Plasmonic Fundamentals and Applications p. 17 (Drude model fit) (2007)

MATERIALS FOR TO / ENZ

- Effective permittivity nearly zero $\epsilon_{\text{effective}} \sim 0$: cloaks, hyperlens etc.
- Real permittivity of metals must be comparable to that of dielectrics
(for example, $\epsilon_{\text{dielectric}} \sim 2$ requires $\text{Re}(\epsilon_{\text{plasmonic material}}) \sim -2$
while $\text{Re}(\epsilon_{\text{Ag}}) \ll -2...$)



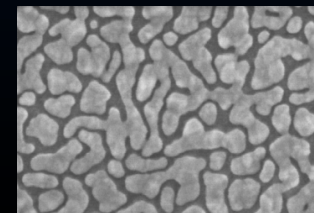
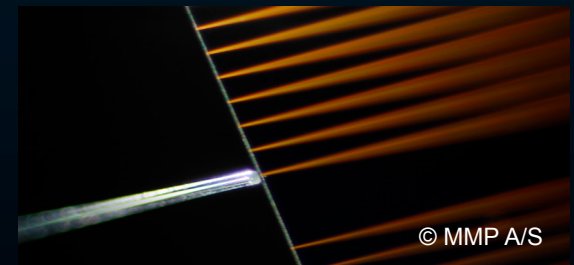
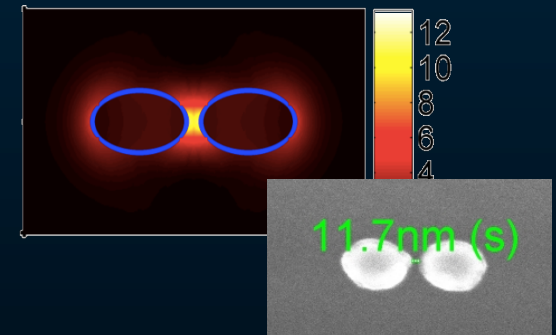
Ag: threshold for uniform continuous films is around 12-23 nm

PLASMONICS&MM: BEYOND GOLD AND SILVER

The vast majority of devices use **gold & silver**

They have many ideal properties, but key drawbacks

- Large losses in the Vis/NIR
- Optical properties are **not tunable**
- Continuous **thin** film growth is difficult
- Nanopatterning increases losses, grain boundaries, surface roughness...
- **Soft materials**
- **Low melting point**
- **Not CMOS-compatible**



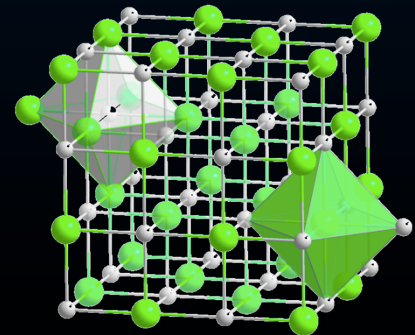
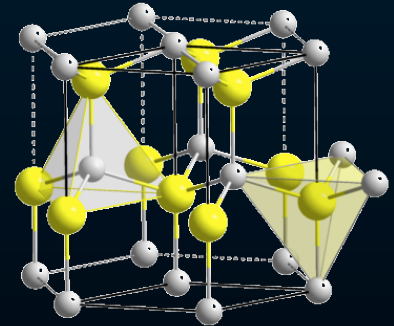
Au & Ag are **NOT** the ideal material for every application

MATERIAL REQUIREMENTS

- **Low loss** components
 - Dielectrics can be nearly loss-less
 - Metals have large losses
- **Adjustable / Tunable** optical properties
Some Metamaterial + TO designs require **comparable magnitudes of ϵ'** of metal and dielectric
 - Epsilon-near-zero (ENZ) materials
 - Effective permittivity nearly zero: e.g. optical cloaks, hyperlens etc.
Engheta, Narimanov, Alu groups
- **Switchable** devices
M. Ren *et al.*, *Adv. Mater.* 23 (2011) 5540; J.Y. Ou *et al.*, *Nano Lett.* 11 (2011) 2142 – Zheludev group
E. Feigenbaum *et al.*, *Nano Lett.* 10 (2010) 2111 – Atwater group
- **SC-compatible** components

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ALTERNATIVE MATERIALS

21 JANUARY 2011 VOL 331 SCIENCE

MATERIALS SCIENCE

Low-Loss Plasmonic Metamaterials

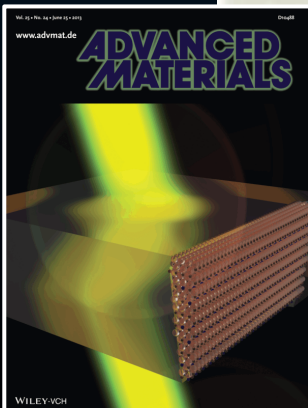
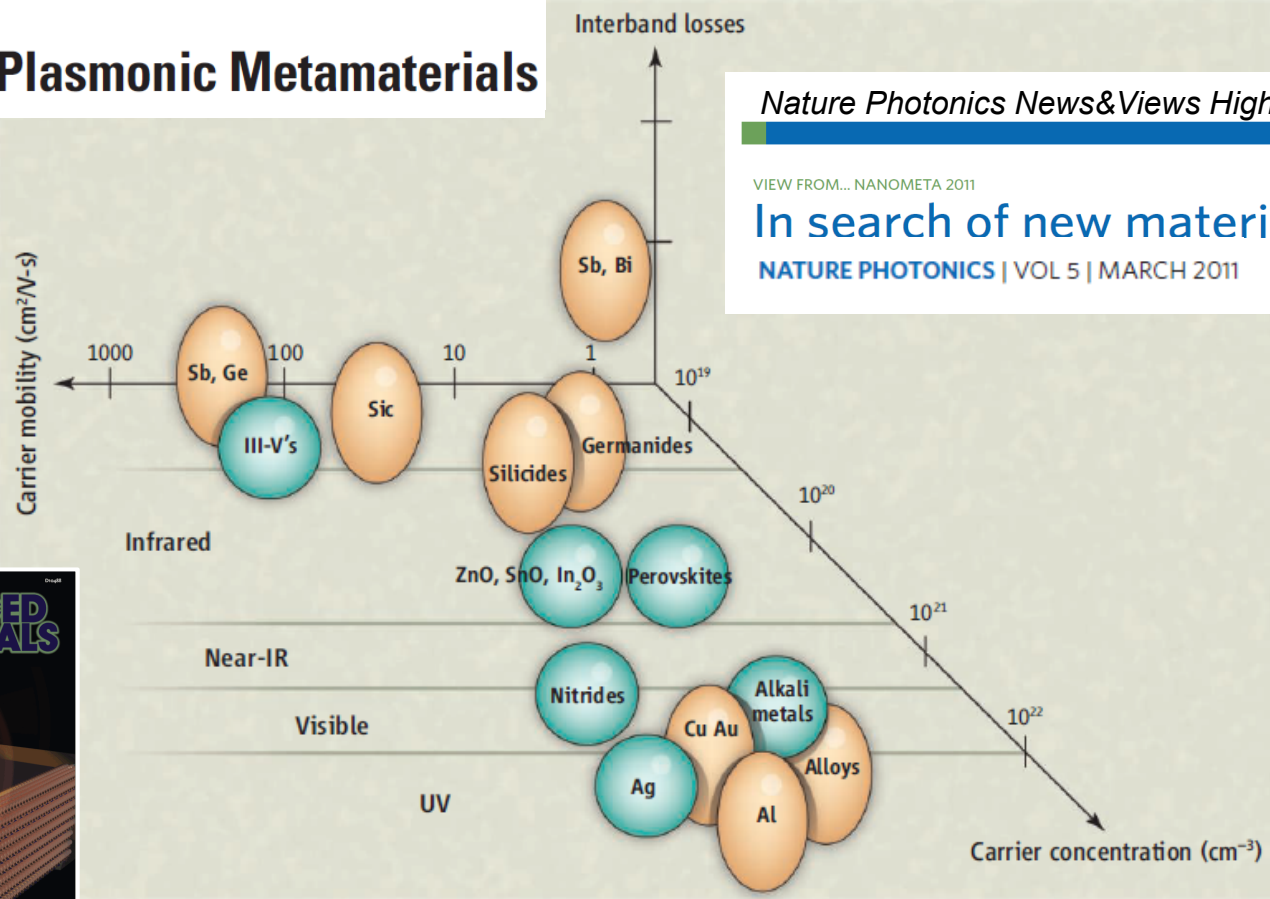
Nature Photonics News&Views Highlight

news & views

VIEW FROM... NANOMETA 2011

In search of new materials

NATURE PHOTONICS | VOL 5 | MARCH 2011



A. Boltasseva and H.A. Atwater, Science **331**, 290 (2011) G. Naik, V. Shalaev, A. Boltasseva, Advanced Materials **25** (24), 3264 (2013)

THE PAST AND PRESENT

Looking for intermediate carrier density materials

The Past																			He			
H																						
Li	Be																B	C	N	O	F	Ne
Na	Mg																Al	Si	P	S	Cl	Ar
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr					
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe					
Cs	Ba	Lu	Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn					
Fr	Ra	Lr	Rf	Db	Sg	Bh	Hs	Mt	Ds	Rg	Cn											

Au, Ag, Cu

The Present																		He											
H											B	C	N	O	F	Ne													
Li	Be											Al	Si	P	S	Cl	Ar												
Na	Mg											K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe												
Cs	Ba	Lu	Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn												
Fr	Ra	Lr	Rf	Db	Sg	Bh	Hs	Mt	Ds	Rg	Cn																		

TiN, TiAlN, ZrN, HfN, ScN, TaN, YN, VN, NbN, CuN, WN

ITO, Ga:ZnO, Al:ZnO, CdO, CdSbO, GaInO, MgInO, SrTiO, SrSnO, CdTeO, BaSnO, SrGeO, InO, TiO, IrO, VO, RuO

CoSi, CrSi, FeSi, HfSi, IrSi, NbSi, NiSi, OsSi, PtSi, PdSi, ReSi, RhSi, RuSi, TaSi, TiSi, VSi, WSi, ZrSi, CaSi, MgSi

RuGe, OsGe, BaGe, SrGe, CaGe, MgGe, CrGe

GaAs, AlGaAs, InGaAs, InP, AlInAs

Li, Na, K

YH

Graphene

MgB

Au, Ag, Cu

A. Boltasseva and H.A. Atwater, Science **331**, 290 (2011)

G. Naik, V. Shalae, A. Boltasseva, Advanced Materials 25 (24), 3264 (2013) + REFS THEREIN

A. Boltasseva, MRS Bulletin (2014)

PLASMONIC MATERIALS

- **Metals** (Ag, Au, Cu, Al, Alkali)
- **Alloys** (Noble-Alkali¹, alloys of noble/transition metals Cadmium/Zinc²)
- **Doped Semiconductors**: Highly doped SCs³, doped conducting oxides (ITO⁴, Al:ZnO and Ga:ZnO⁵, ICO)
- **Intermetallics** (nitrides, germanides, oxides, hydrides⁶...)
- **Graphene** and other **2D systems** (MoS₂ and other)
- **Dielectrics!**

1: M. G. Blaber et al., J.Phys. Cond. Matter. 21, 144211 (2009), 2: D. A. Bobb et al., Appl. Phys. Lett. 95, 151102 (2009); 3: A. J. Hoffman et al., Nature Mater. 6, 946 (2007); 4: C. Rhodes et al., J. Appl. Phys. 100, 54905 (2008); M.A. Noginov et al., Appl. Phys. Lett. 99, 021101 (2011); 5: LPR 4, 795 (2010), Phys. Status Solidi RRL 4, 295 (2010), Metamaterials 5, 1 (2011), OMEx (2011), Advanced Materials 25 (24), 3264 (2013); 6: Nano Lett., 2014, 14 (3), p 1140, H. Giessen group also work by groups of N. Halas, H. Atwater, N. Zheludev, D. Basov, J. Garcia de Abajo, H. Giessen, C. Murray, O. Muskens

METALS

Ag – Conventional Plasmonics, usual choice

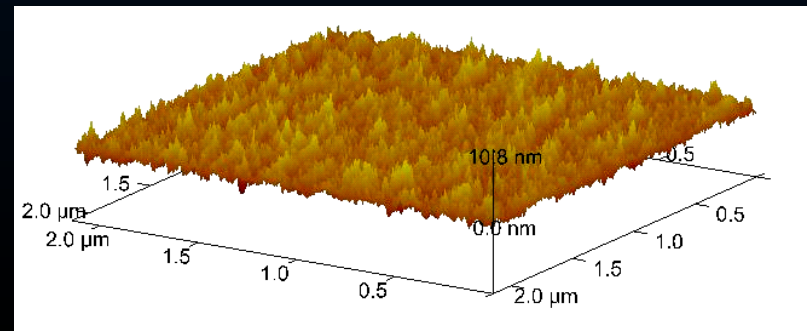
- Low loss
- Standard physical vapor deposition (PVD) methods + chemical methods
- But *degrades* in air

Au – Second Best for VIS, NIR

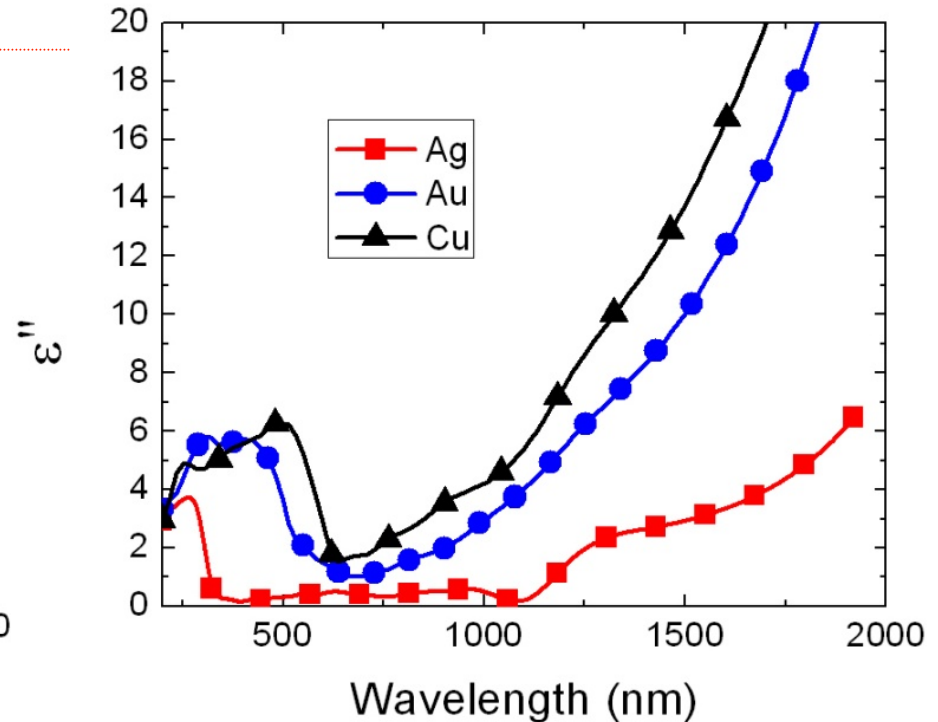
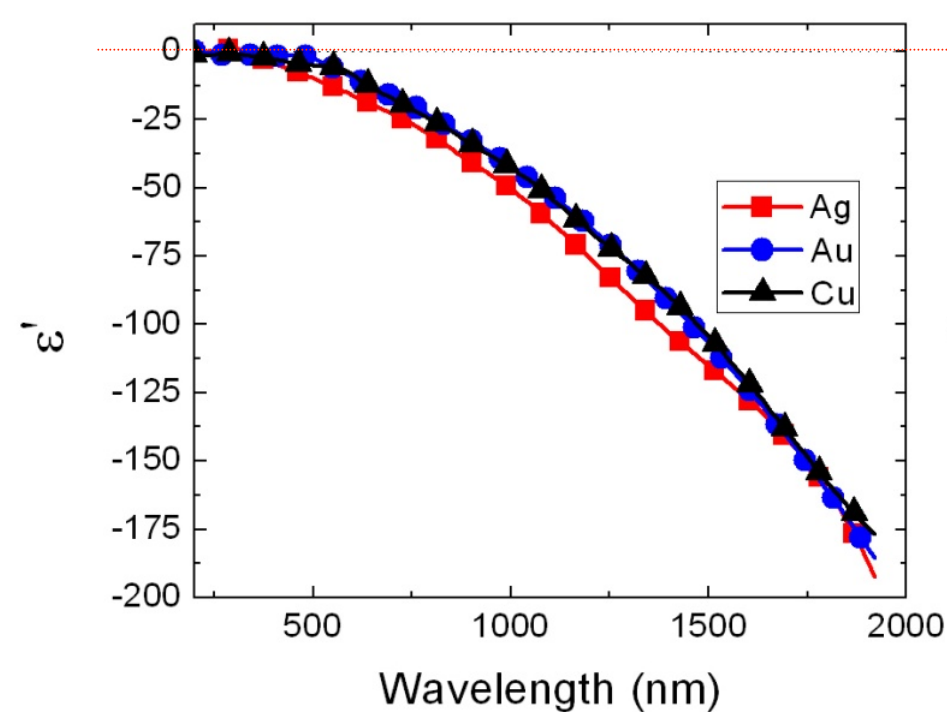
- Acceptable loss but *interband transition* (5d-6p) within VIS range
- Standard PVD methods + chemical methods: Chemically stable
- Continuous film at thickness of 2-7nm

Cu – Ok for VIS (similar to Au)

- High conductivity + low cost
- But prone to surface *oxidation*



Ag, Au, Cu

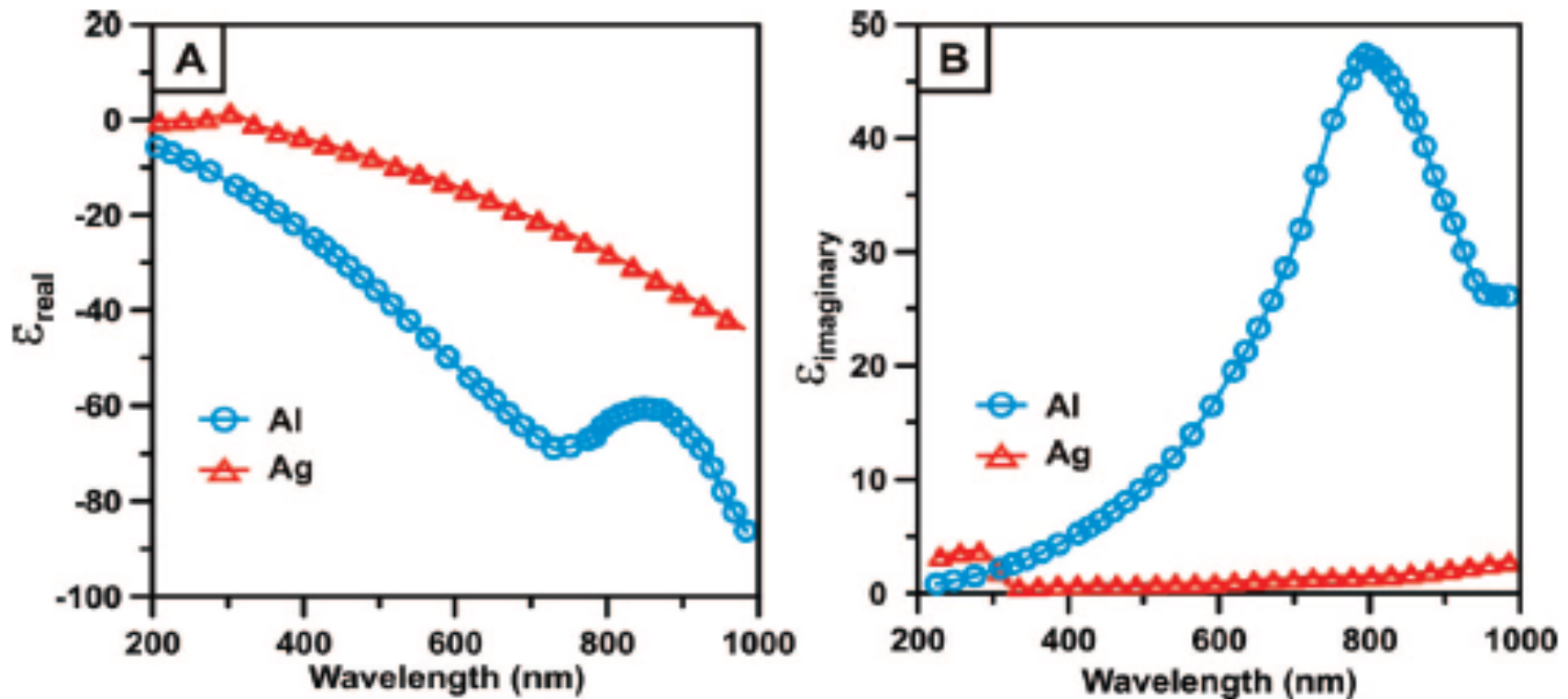


Cu – similar to Au 600-750 nm **CMOS compatible!**
fabrication is challenging (easily oxidizes)

ALUMINUM

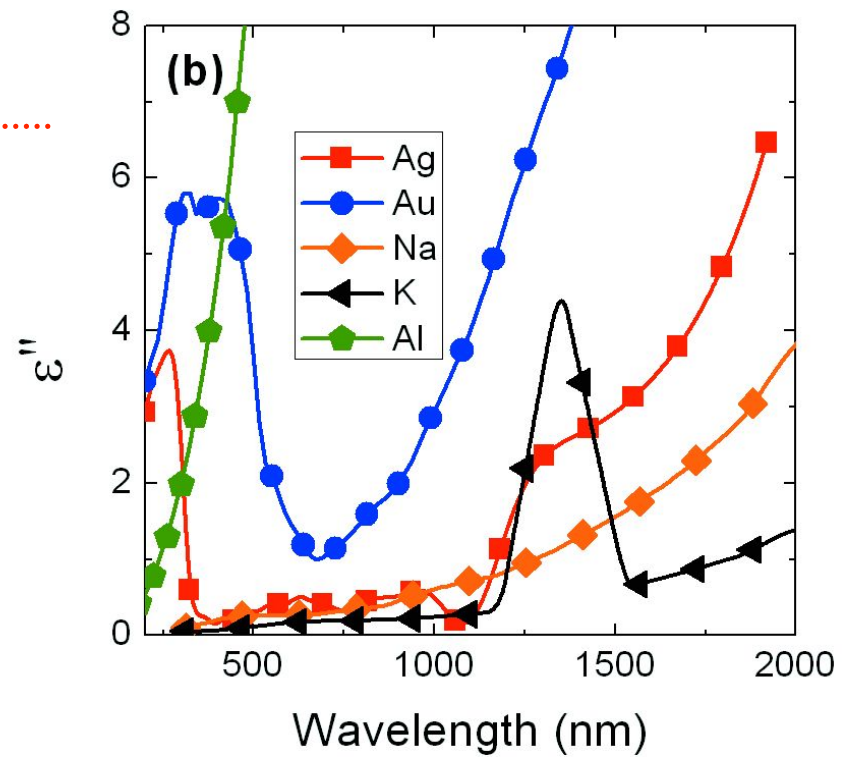
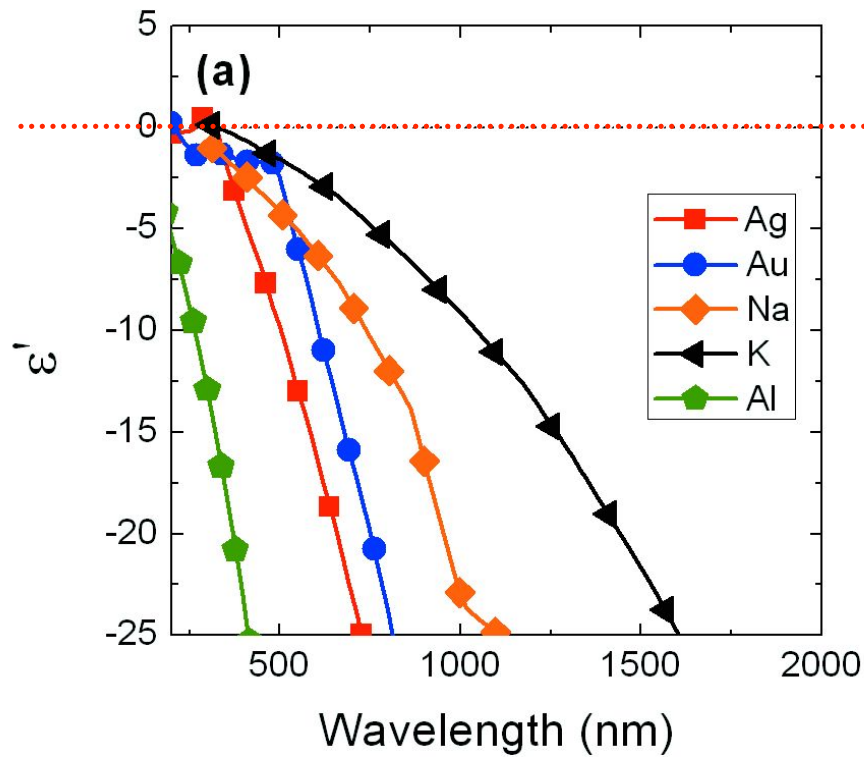
Al – Higher loss in VIS + NIR

- Best for short wavelengths (**still plasmonic below 200 nm!**)
- Prone to surface *oxidation* (Al_2O_3 2.5~3nm)



ALKALI

Alkali (Sodium, Potassium) – Lowest losses, closest to free-electron gas
 - Very *reactive* (ultra-high vacuum 10^{-19} Torr requirement, passivation)



ALLOYS: IMPROVING METALS

Improving Noble Metals:

- To shift interband transitions to another (unimportant) part of the spectrum
- By alloying two or more elements to create unique band structures that can be fine-tuned by adjusting the proportion of each alloyed material

Noble-Transition Metal Alloys

Bivalent transition metals (Cadmium and Zinc) contribute one extra electron to the free-electron plasma n-type doping $\Rightarrow$

- Increasing of ω_p
- Shifting the threshold for interband transitions
- Reducing the absorption at a specific wavelength

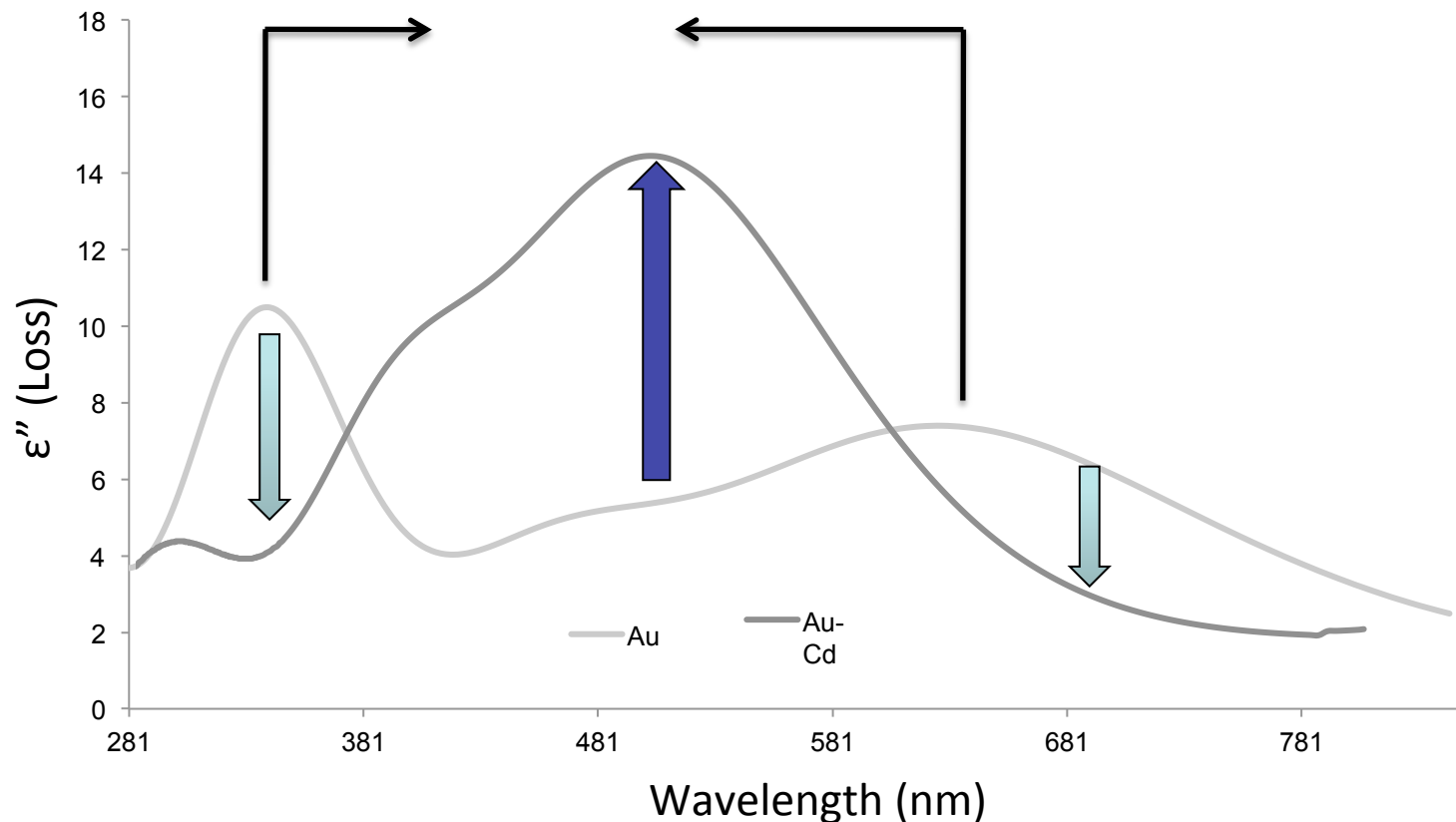
“Band Engineering”

NOBLE-TRANSITION ALLOY

Cadmium + Gold $\Rightarrow$ Additional electron to free electron gas

Shift of the Lorentz resonance peaks $\Rightarrow$ Tuning of the optical parameters

Optimum – 3.3% Cadmium in Gold



“LESS-METALLIC” MATERIALS?

- Metals: Too large carrier concentration *METALS ARE TOO METALLIC...*
 - Large plasma frequency (ω_p)
 - $\omega_p \propto \sqrt{n}$: $n \sim 10^{22} \text{ cm}^{-3}$ in metals
 - Large loss ($\epsilon'' \propto \omega_p^2$) + large magnitude of ϵ'

SEMICONDUCTORS → “METALS”

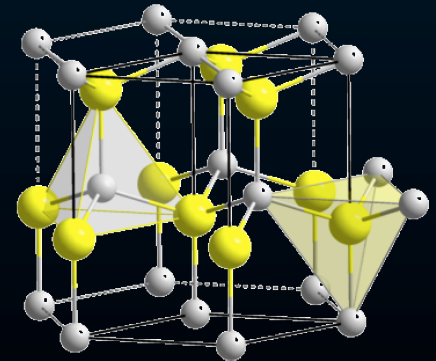
- Semiconductors: **Doping** can control carrier concentration
 - Conventional semiconductors: too low carrier concentration (dielectrics)
 - Doping density of 10^{21} cm^{-3} could produce $\epsilon' < 0$ in NIR

METALS → TO “LESS-METALS”

- Lower carrier concentration in metals
 - Abstract electrons by non-metal inclusions
 - Non-stoichiometric: controllable properties

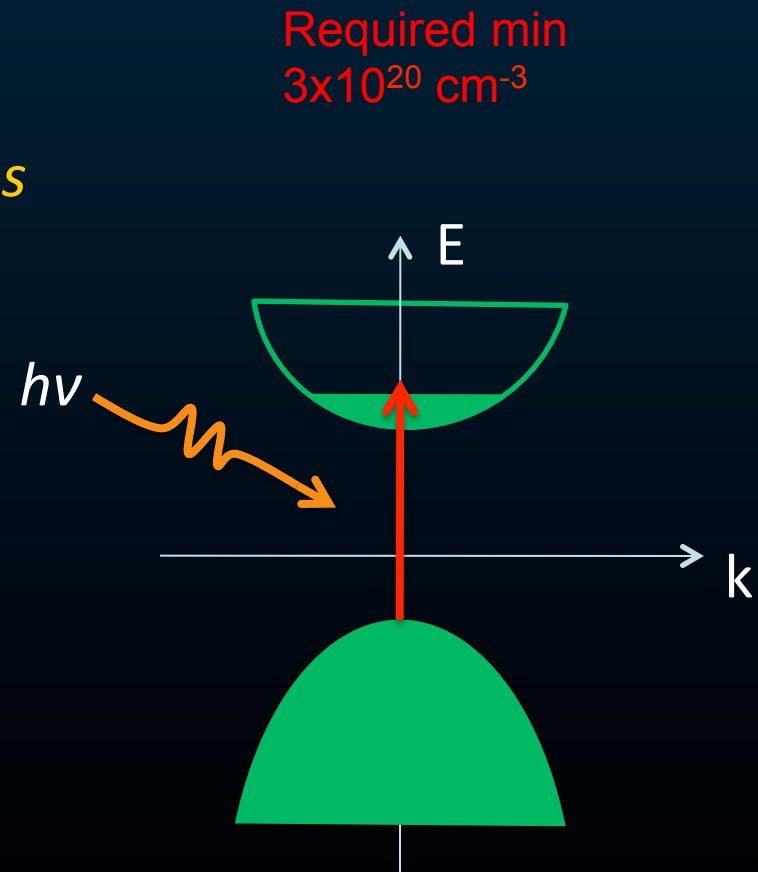
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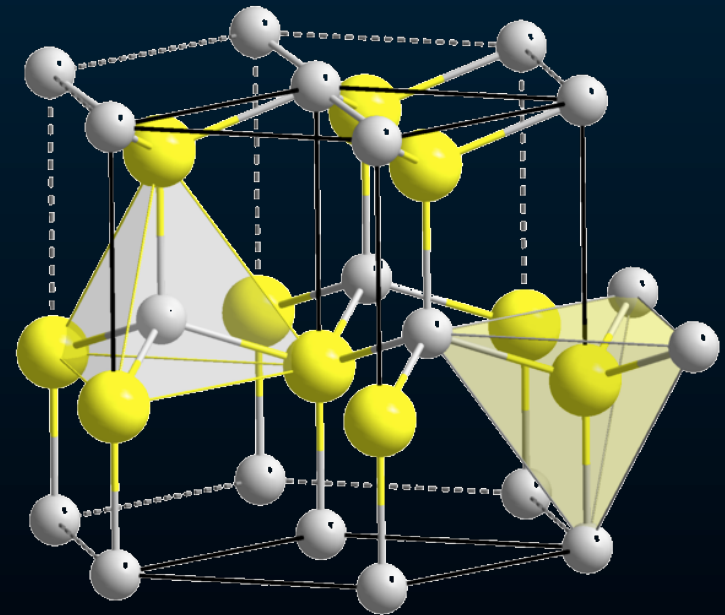
SEMICONDUCTOR-BASED “METALS”

- Make semiconductors more metallic:
Increase carrier concentration to 10^{21} cm^{-3}
- Wide Bandgap Semiconductors:
Negligible interband transition losses
- Bandgap should be larger than frequency of interest
Material Bandgap (eV):
Si - 1.12, GaAs - 1.42, SiC - 2.36-3.05
- Large carrier mobility:
Low damping losses



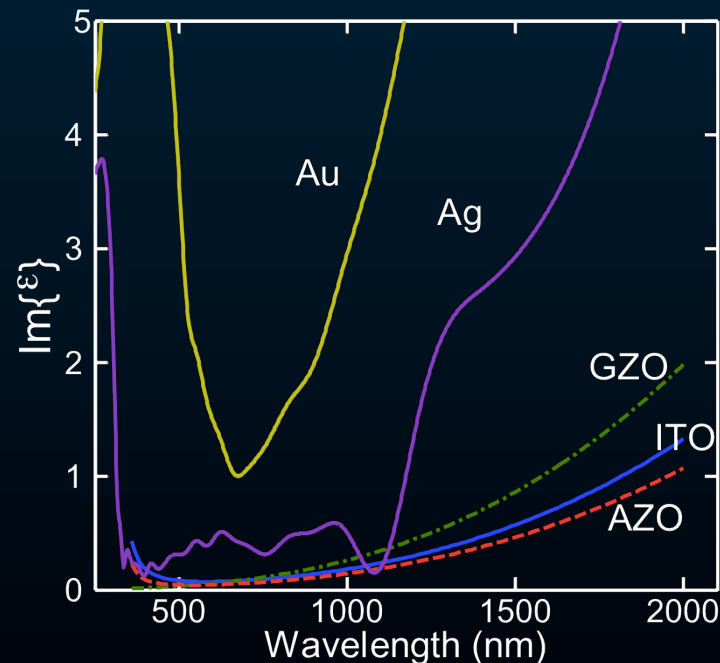
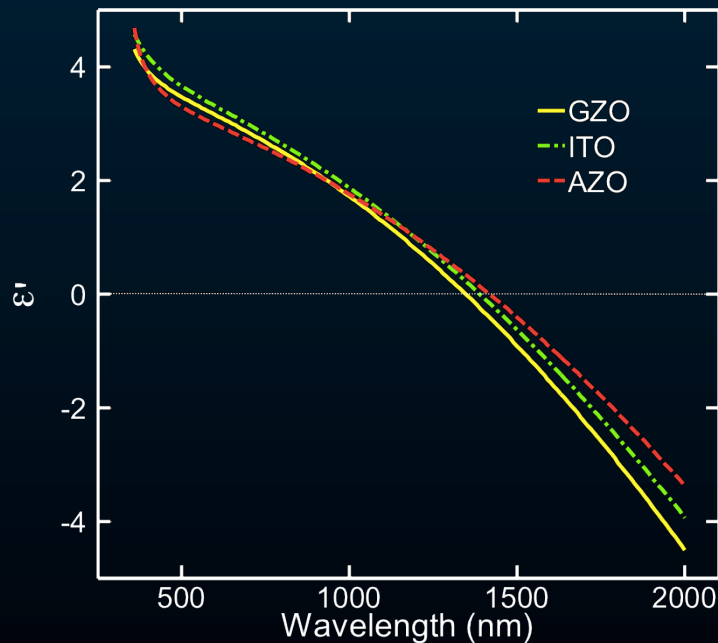
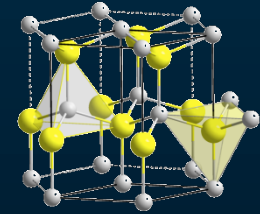
ZINC OXIDE

- II-VI semiconductor
- Wide band-gap of 3.37 eV at 300 K
- Applications:
 - Display flat panels
 - Piezo-electric devices
 - Paints, anti-corrosive coatings
 - Bio-compatible devices
 - Optoelectronic devices
 - Gas-sensing
- Heavy doping:
 - Al or Ga (up to 10^{21} cm^{-3})
 - Challenging



SEMICONDUCTOR “METALS”: TCOs

- DOPED ZINC OXIDE: Wide band-gap (3.37 eV@300K)
- Al or Ga (up to 10^{21} cm^{-3})
- **Can be adjusted/tuned!**



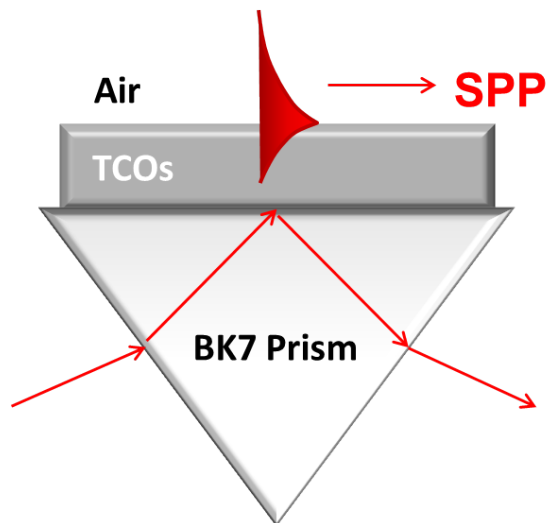
Also see :
 O. L. Muskens
 H. A. Atwater
 M. A. Noginov
 C. B. Murray
 D. J. Milliron
 V. J. Sorger
 R. P. H. Chang
 M. Wegener
 S. Franzen
 T. W. Odom
 V. A. Podolskiy

AZO: Lowest Drude damping, Longest cross-over wavelength ($5 \times 10^{20} \text{ cm}^{-3}$)

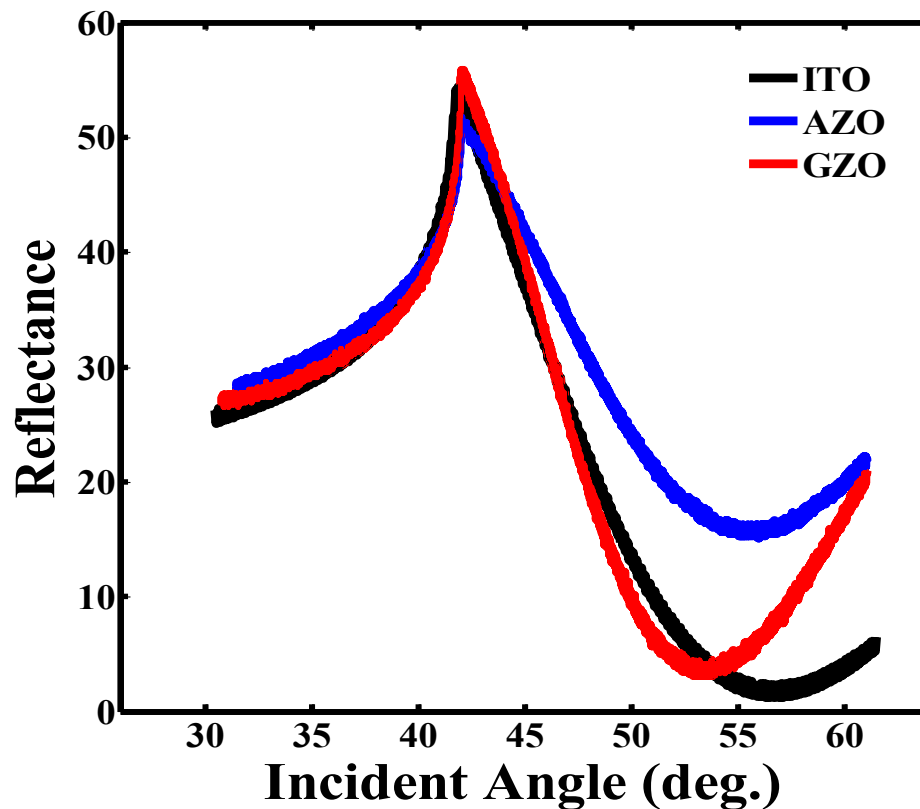
GZO: Cross-over wavelength as low as $1.2 \mu\text{m}$

Theoretical studies: with Norfolk and Navy Research Lab

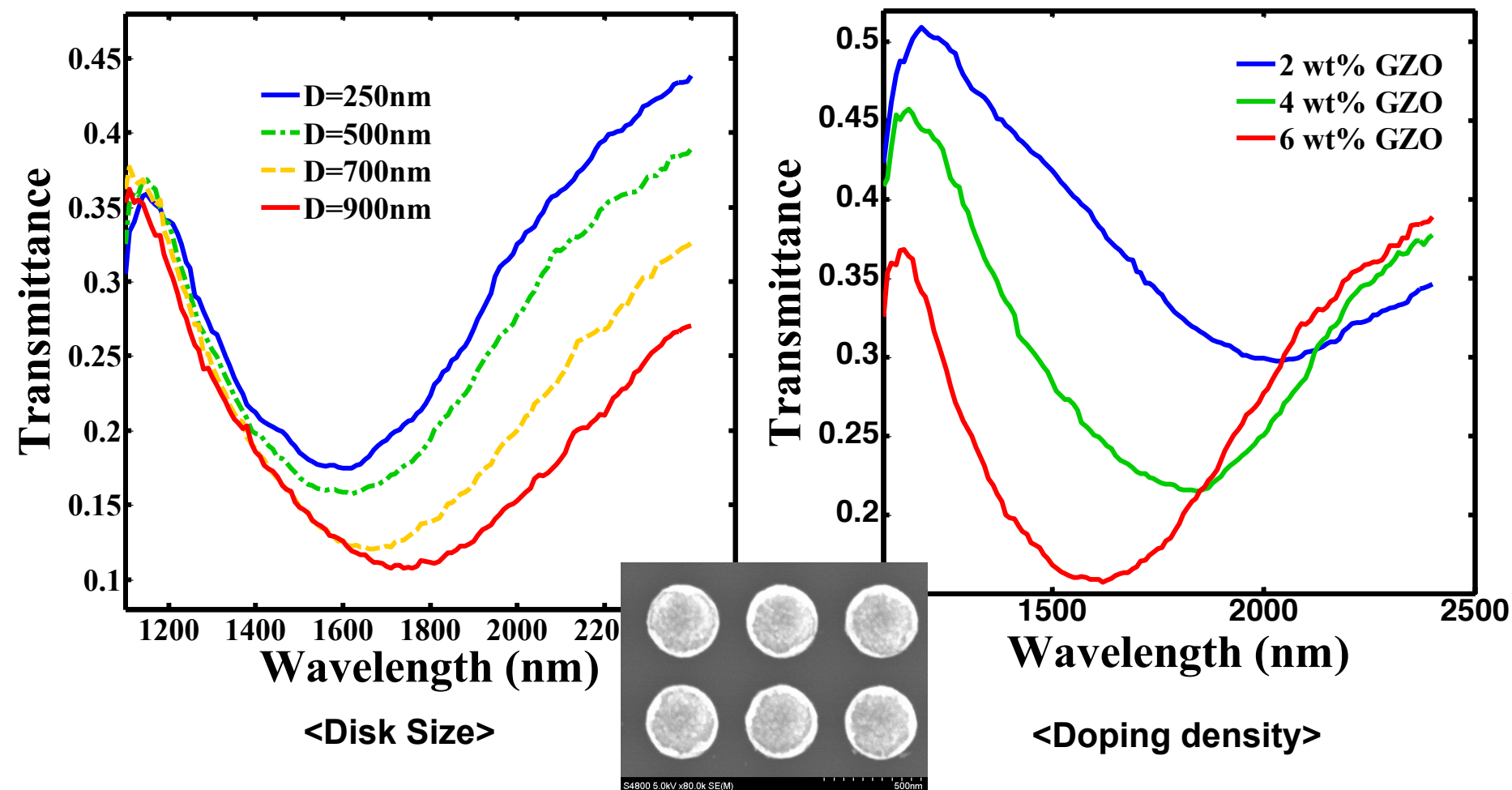
SPPs ON TCO FILMS AT 1.55 μm



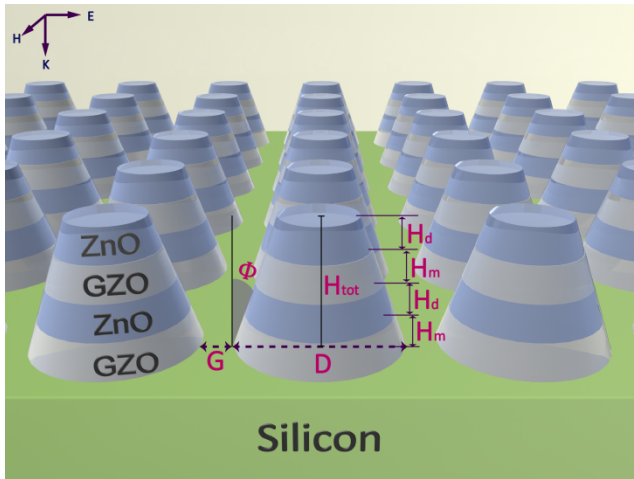
- TCO is directly deposited onto BK7 glass prism
- $\text{Re}\{\epsilon_{\text{TCO}}\} < -1$ (at 1.55 μm)
- Angular reflectance shows dip at angles corresponding to excitation of SPPs



TCO LSPR STRUCTURES (Size and Doping)



GAP SP IN TCO/DIELECTRIC/TCO

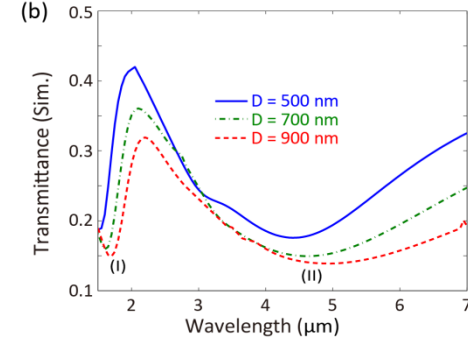
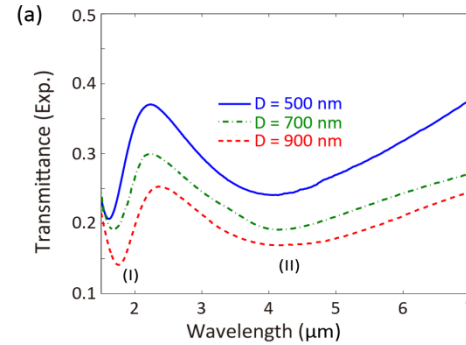


- $H_{\text{ZnO}} = 40 \text{ nm}$, $H_{\text{GZO}} = 120 \text{ nm}$
- Metal : Gallium doped ZnO
- Dielectric : Undoped ZnO

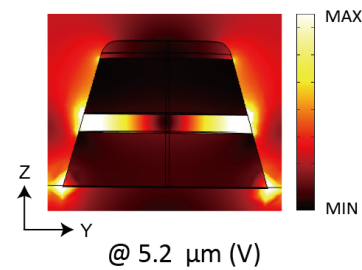
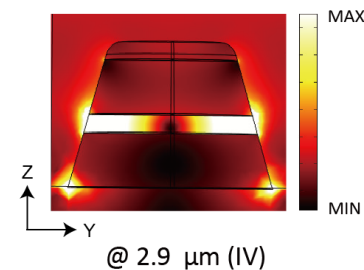
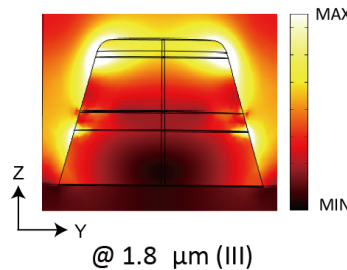
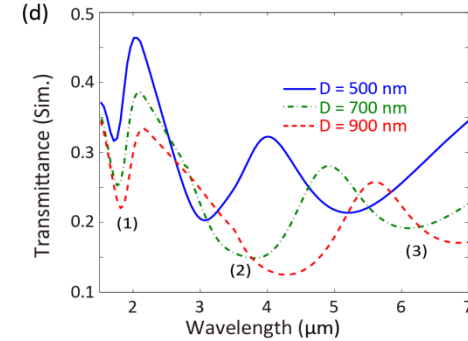
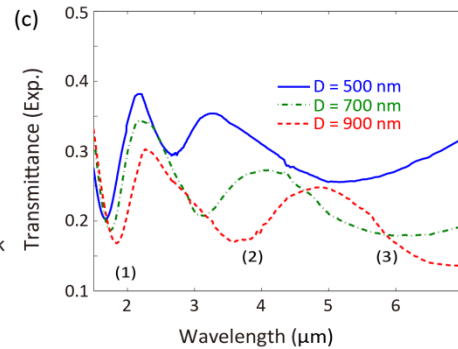
- **1.8 μm : LSPR**
- **2.9 μm : Gap Surface Plasmon Resonance**
- **5.2 μm : LSPR + GSPR**



GZO Nanodisk

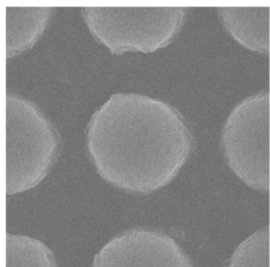


ZnO / GZO Nanodisk

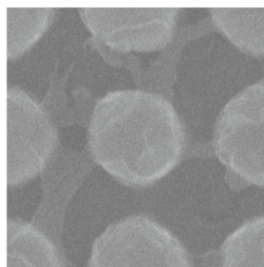


Surface Enhanced Infrared Spectroscopy

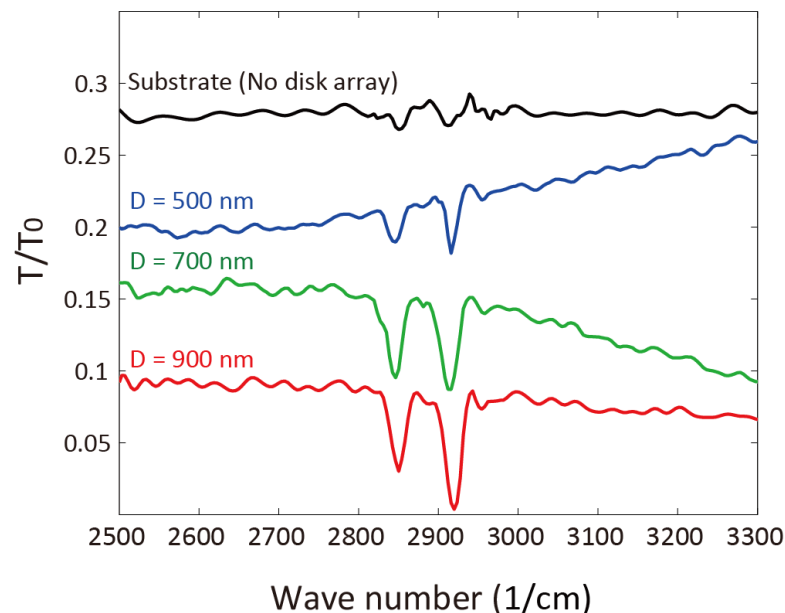
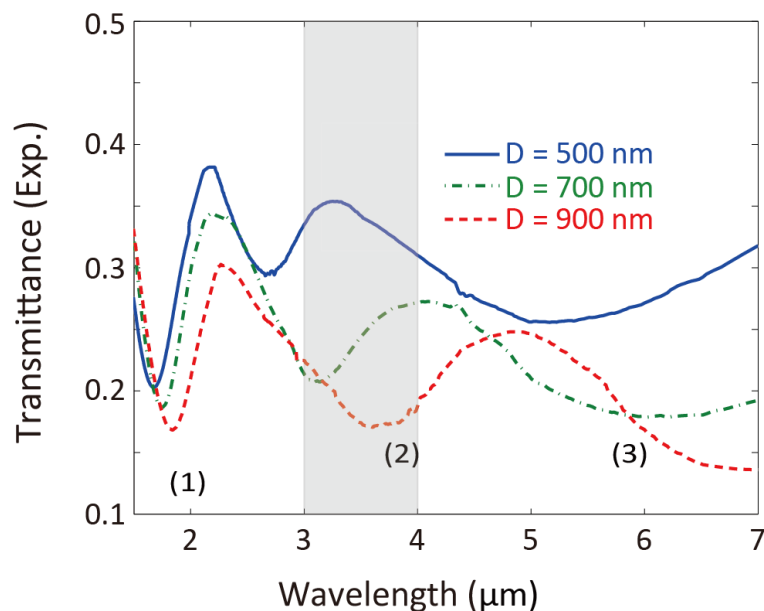
Nanodisk without ODT layer



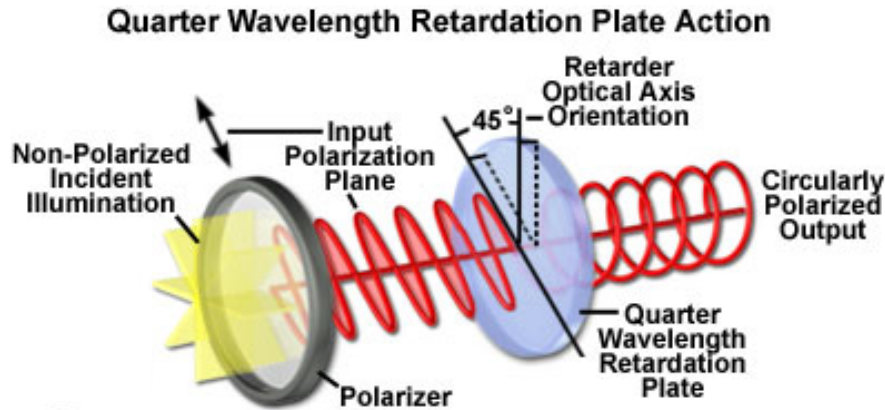
Nanodisk with ODT layer



- ❑ Octadecanethiol (ODT) Polymer layer (20nm)
- ❑ Absorption from vibrational modes of ODT molecules are located very close to the GSP resonance
- ❑ Strong enhancement of absorption due to interaction with GSPR on MIM TCO based nanodisk resonator



METASURFACES WITH CERAMICS With Andrea Alu

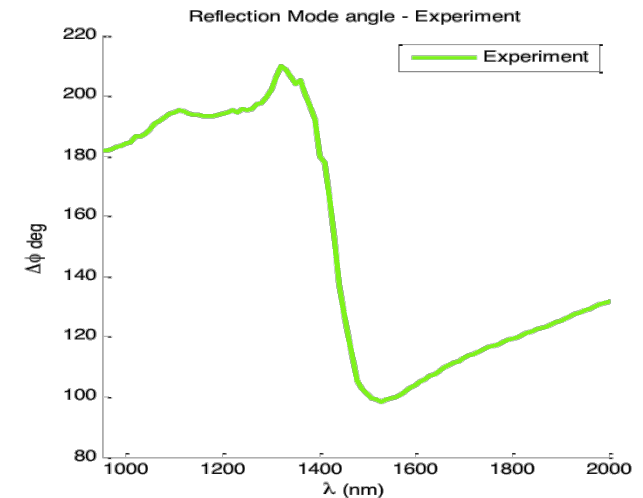
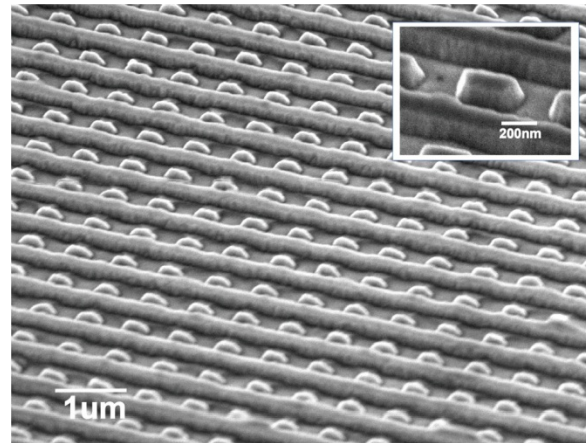
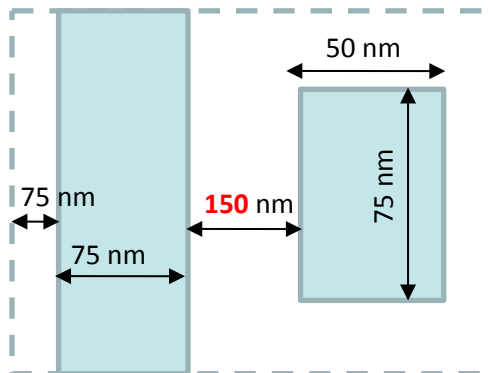


Current QWP

- ✓ Bulk birefringent material with optical anisotropy
- ✓ Narrow band

QWP metasurface

- ✓ Fabrication simplicity/1D design
- ✓ Nano-scale
- ✓ Broadband



GZO metasurface and Phase difference (Δ) of reflected light between two orthogonal polarizations (s and p) at 18° angle of incidence

See work by Hasman, Capasso, Zheludev, Alu groups

EPSILON NEAR ZERO (ENZ)

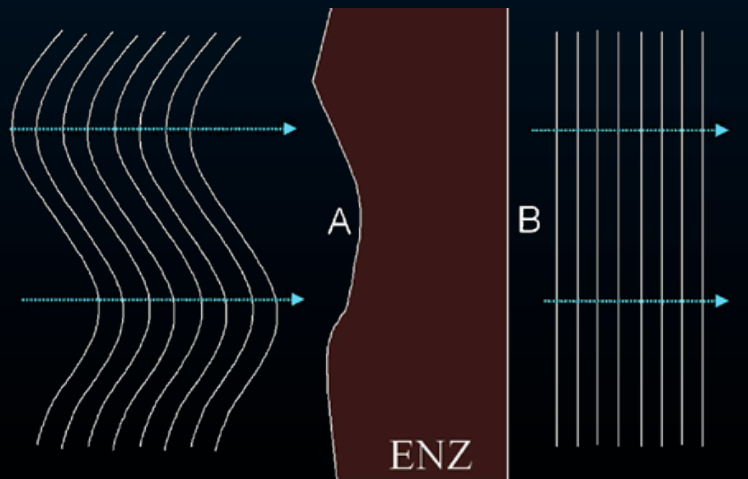
CONCEPT:

- Near Zero Refractive index (n) : Light propagates with almost **no phase advance**
→ Very small phase variation over a physically long distance
- High impedance** with the surrounding environment $Z = \sqrt{\mu/\epsilon}$
→ Directive radiation or **Isolation** of devices for on-chip nanophotonic devices

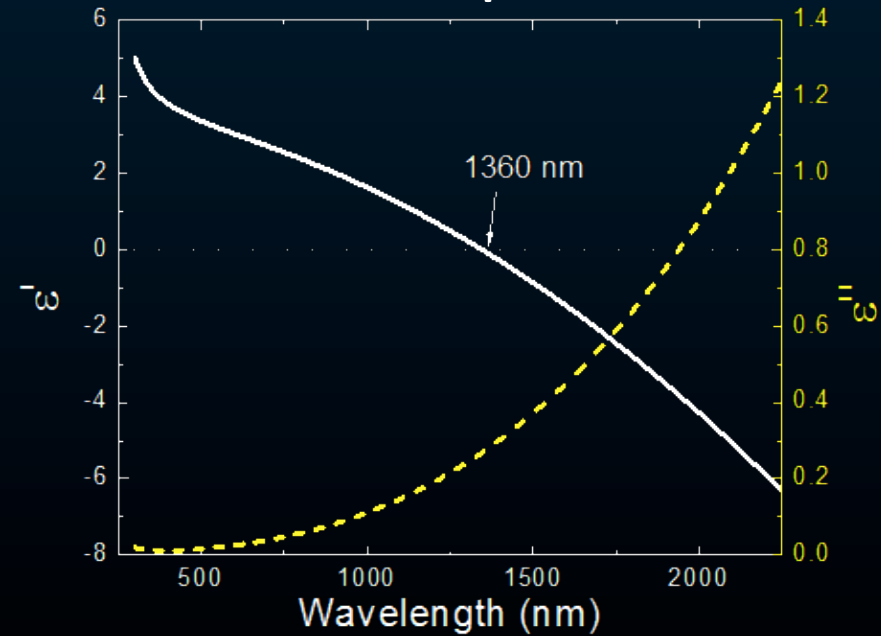
TCOs as ENZ :

Naturally occurring **ENZ medium** with low losses in NIR

Tunable ENZ by doping



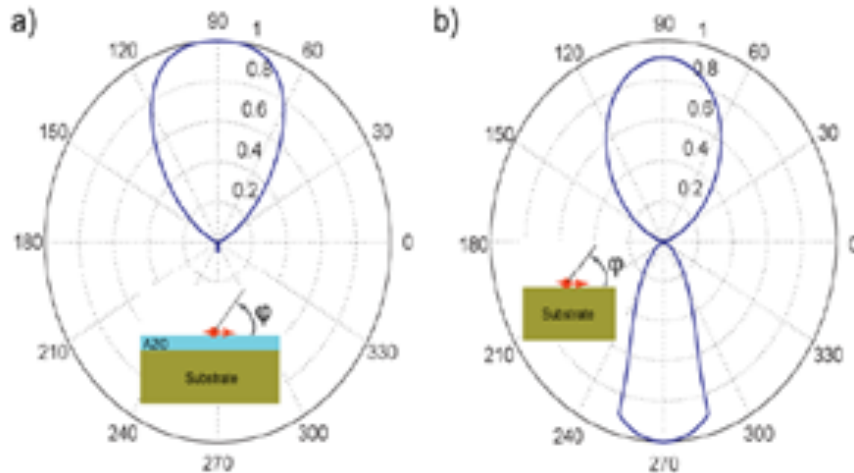
TCO: Al doped ZnO



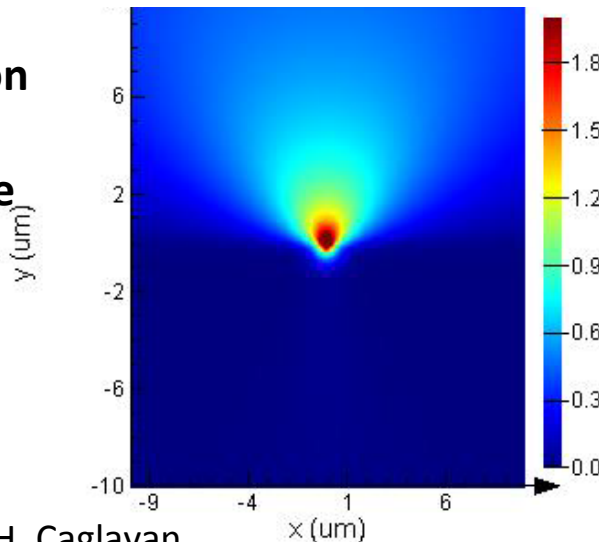
ENZ at around 1360 nm wavelength

See work by Engheta, Alu, Muskens and other groups

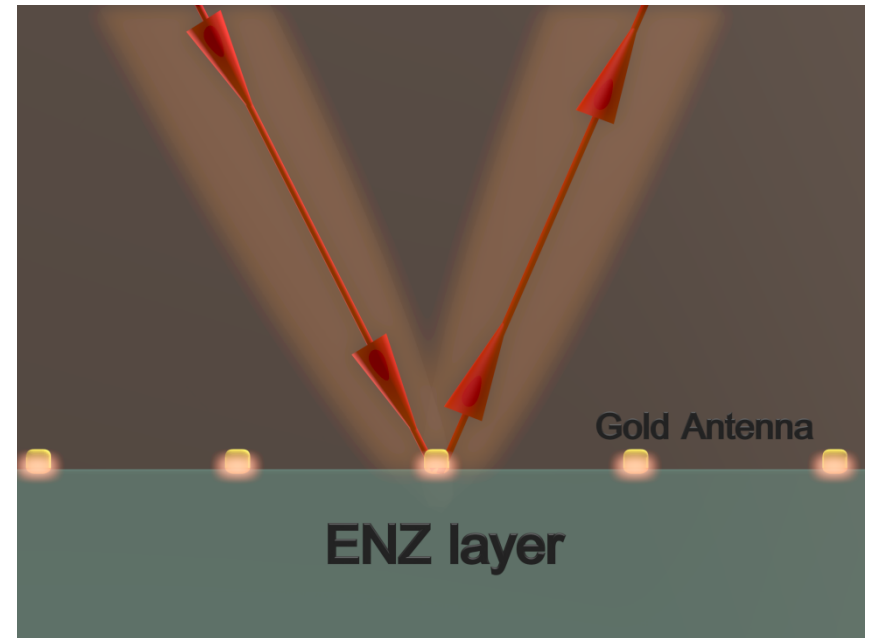
ANTENNAE/EMITTERS ON ENZ



Dipole on
ENZ/air
interface

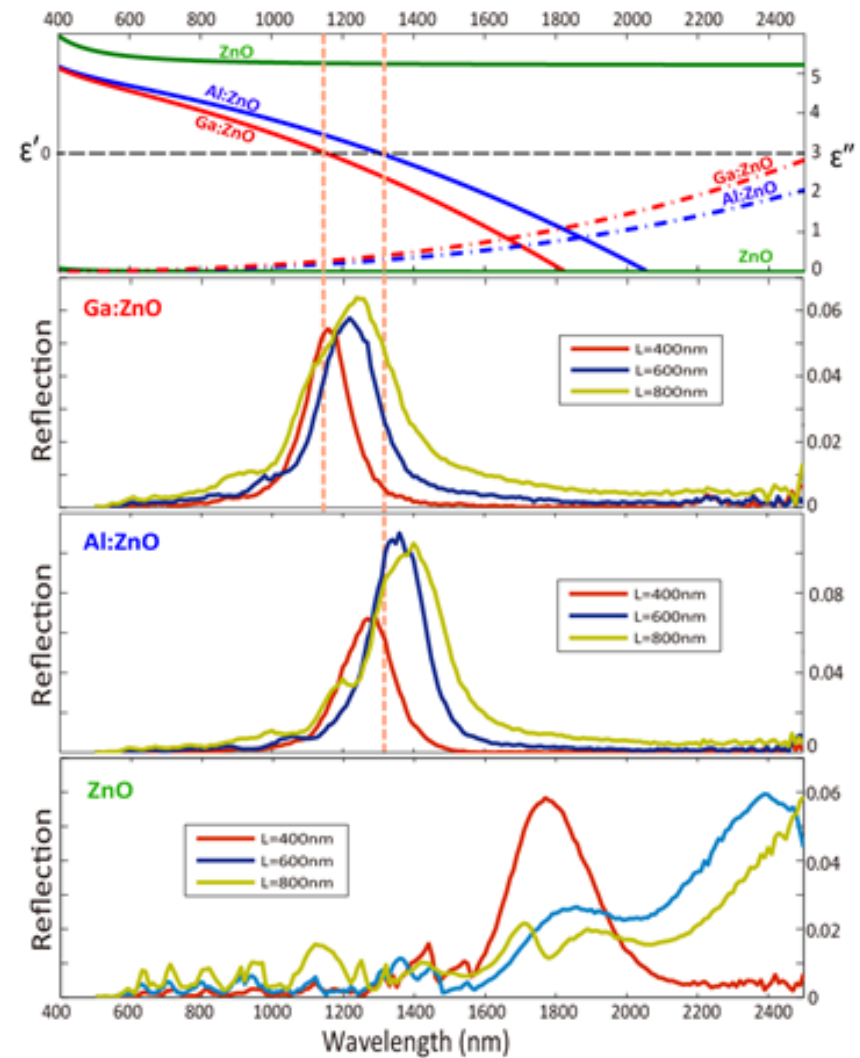
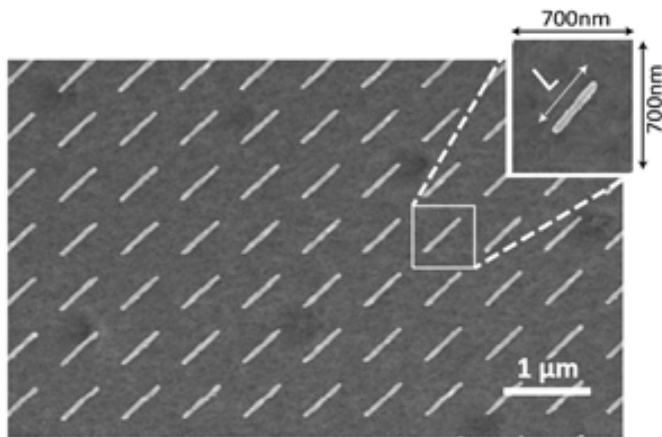
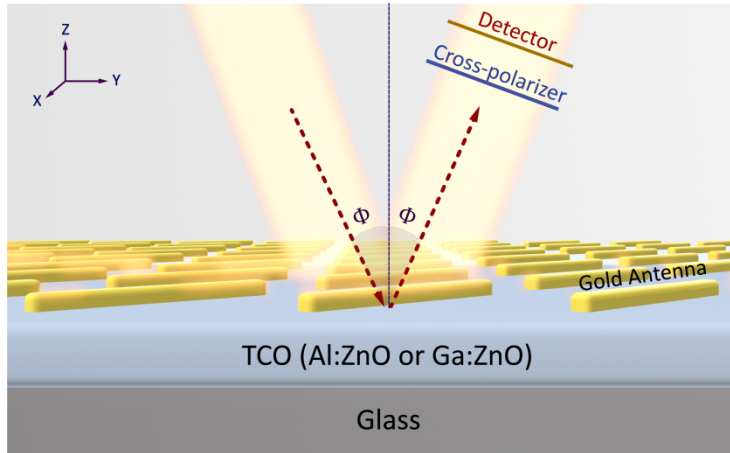


By H. Caglayan



ENZ substrates alter radiation
pattern and pin antenna
resonances to ENZ wavelength!

ANTENNAE ON ENZ

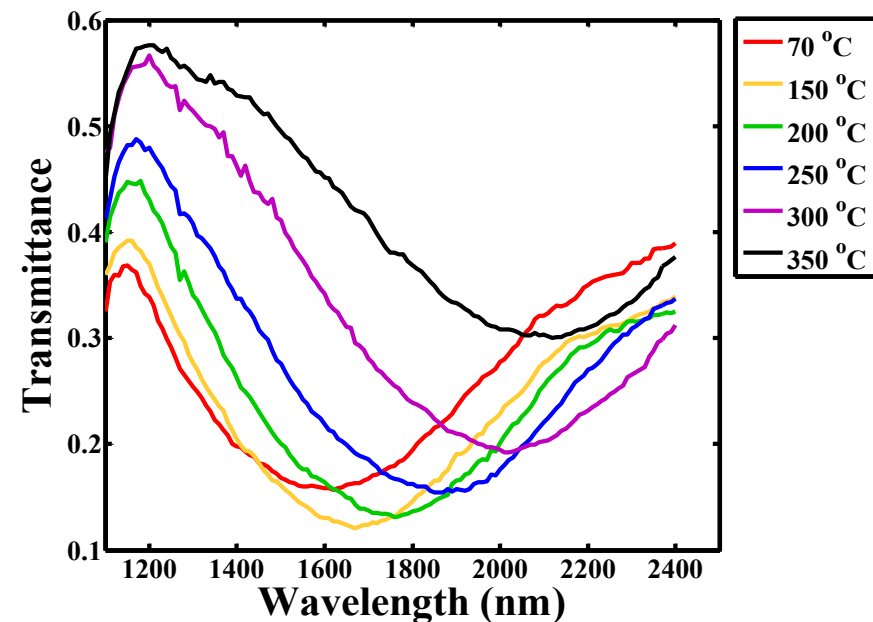
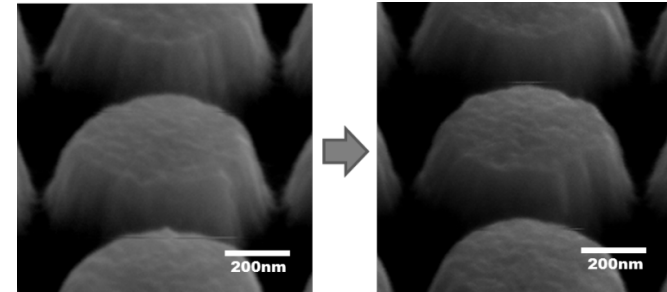


TUNING LSPR IN TCOs

- Resonance **tuning** by anneal process
- Nitrogen and oxygen anneal reduces carrier concentration
- Nitrogen anneal reduces defects and improves damping losses

Approaches:

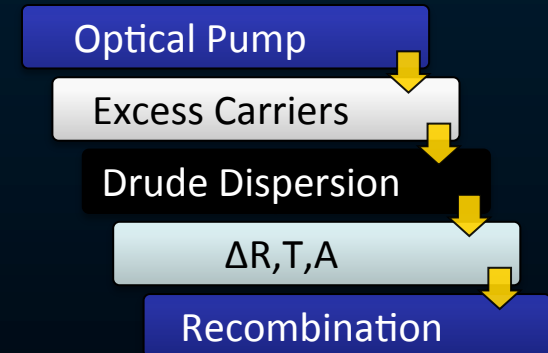
- Doping concentration change during solution-based synthesis (AZO)
- Dynamically change doping level by electrochemical means (ITO)
- Electrical means



TUNABILITY OF TCOs

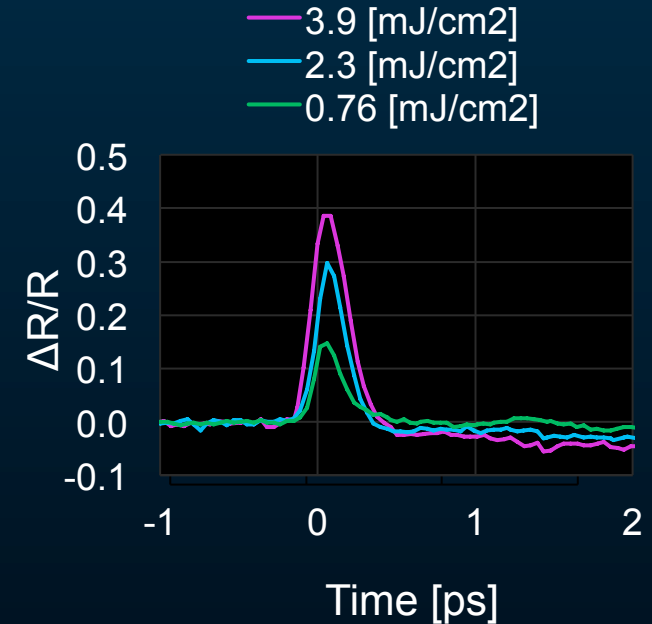
- Transparent conducting oxides are known for their **dynamic nature**
 - **Electrical**
 - **Optical**
- Reports of dynamic devices using TCOs, little evidence for the change of carrier concentration
- Use pump-probe techniques to investigate **ALL-OPTICAL tuning** of TCOs

Free Carrier Effect



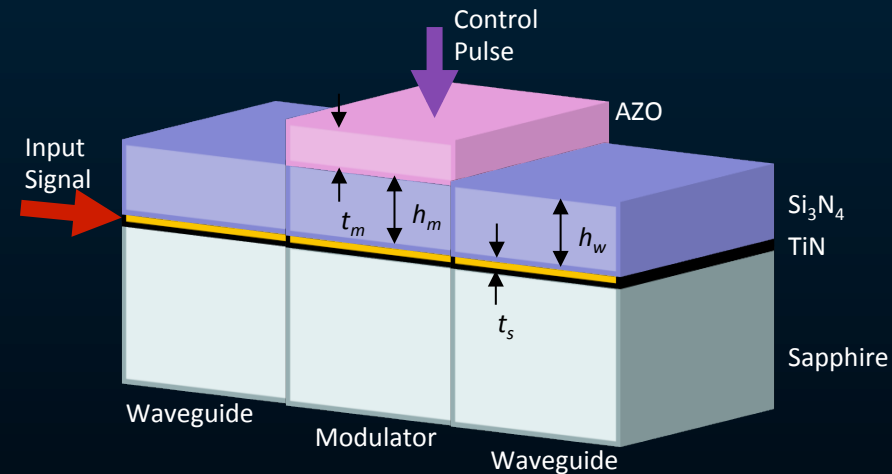
PUMP-PROBE RESULTS

- Experimental results:
 - Large change in R & T (40% & 30%)
 - Ultrafast response zero-to-zero in < 1 ps
 - **Small energy required**
- The **large response** is due to ENZ operation
- **Ultrafast recombination** is believed to be the result of deep level defects which arise due to the growth procedure
 - Similar effect noted in low-T GaAs
 - However, this effect is still 2-3x faster



ALL-OPTICAL MODULATOR

- The extracted values were used to design a high-speed modulator
- Based on the solid-state TiN waveguide
- Modulation achieved through two processes
 - Absorption
 - Mode disturbance
- Mode in waveguide exists only for a balanced effective index
- Modification of the AZO index disturbs this balance so the mode no longer is supported

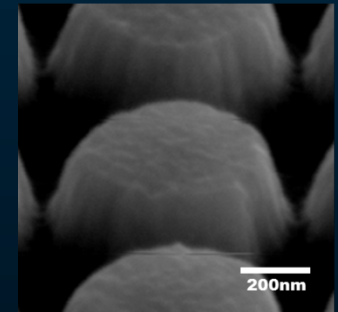
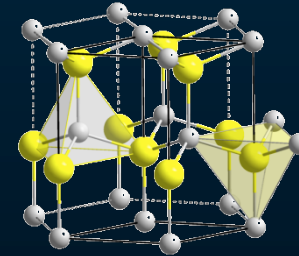


See modulator work by Juerg Leuthold,
Volker Sorger, Harry Atwater, Mark
Brongersma

NOVEL TUNABLE/SWITCHABLE DEVICES

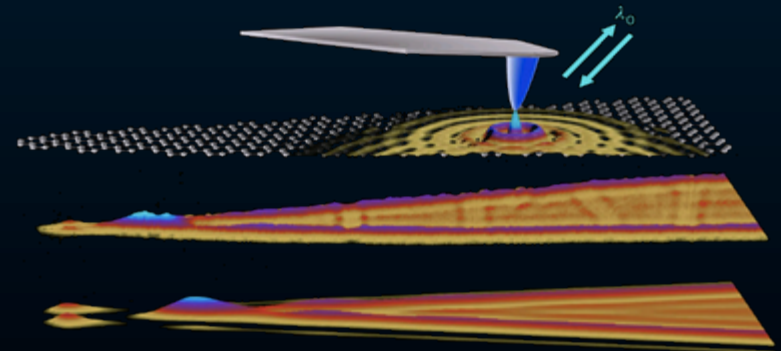
TRANSPARENT CONDUCTING OXIDES

- *Plasmonic materials in NIR*
- *Tune plasma frequency by doping*
- *Great switching opportunities*
- *Standard fab, SC-compatible*



GRAPHENE

- *Strong electrical tunability*
- *Highly confined plasmons (40-60 times smaller than λ_0) at IR*



Applications

- *Optical Modulators, NIR/VIS photodetectors*
- *Lasers, THz polarization controllers*

TCOs: NEED FOR THEORY & MODELING

Doping of ZnO substantially affects

- Lattice parameters
- Band structure

Optical response mechanisms in Ga:ZnO

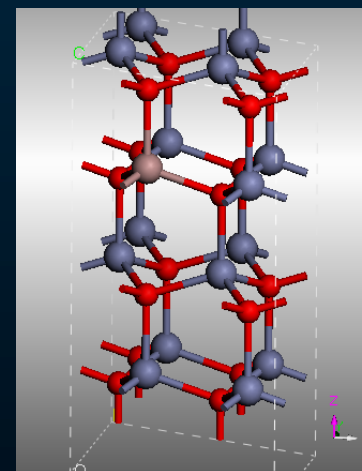
- Burstein-Moss – Excitons –
- Atomic structure distortions – Alloying effects

Modeling and Simulation (NSU)

- Lattice expansion with Ga-doping
- Density of States : Strong charge redistribution due to d-Ga electrons

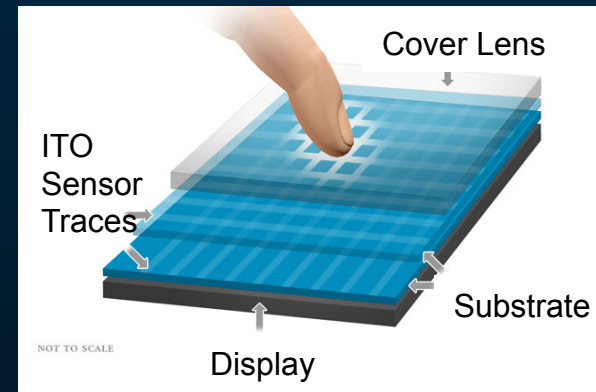
In highly doped materials the ATOMIC STRUCTURE TRANSFORMATIONS and ALLOYING EFFECTS provide increasingly important contributions to optical response

Ga: ZnO



TCOs AS DYNAMIC MATERIALS

- TCOs with extremely high dopant solubility
 - 10^{21} cm^{-3}
- Numerous advantages for plasmonic applications
- **Mature fabrication** processes
 - Sputtering, PLD, ALD, CVD, etc.
- **Non-stoichiometric material**
 - Plasma frequency highly tunable from VIS to NIR (ex. ITO 600 - 1600 nm)
- AZO and GZO can have significantly lower permittivity at telecommunication wavelengths



ITO-based touch screens



IGZO-based highly resolved flexible screen

TCOs: OUTLOOK

- TCOs: AZO, GZO, ITO, ICO...
- Great potential for nanophotonic/plasmonic applications in NIR!
- *Tunable plasma frequency by doping*
- *Great switching opportunities (electrical/optical)*
- *Low loss*
- *Small adjustable real part of permittivity*
- *Mature fabrication process*
- *Compatibility with SC-processes and other materials (TCOs, Graphene, YH2)*